IN THE CLAIMS:

Please amend claim 19 and add new claim 37, as follows:

1-18. (Cancelled)

19. (Currently amended): A device for treating the surface of containers with a

plasma, comprising a kinematic system for the transport of the containers and a plurality of

plasma generators operating at atmospheric pressure and arranged in parallel so as to treat

simultaneously a plurality of containers, each generator designed for carrying out a full treatment

of one container at a time, the plasma generator comprising a treatment gas supply system and an

electrical power supply system comprising at least one interrupter transistor functioning as an

interrupter, or an LC adapter, adapted for supplying current in pulses and wherein said plasma

generator further comprises one external lower electrode for gripping said container and a

rotational mechanism ensuring the rotation of the container during its treatment.

20. (Previously presented): A device according to claim 19, wherein each generator is

provided as a column having a diameter or a width close to or slightly greater than the diameter

or the width of a container.

21. (Previously presented): A device according to claim 19, wherein the power supply

system includes or is connected to a control unit adapted to control the amplitude of the pulses of

electric current, the slope of the leading edge of these pulses, their frequency and the time

elapsed between two successive pulses.

Amendment After Final Office Action mailed December 12, 2007 Serial No. 10/510,999 22. (Previously presented): A device according to claim 19, wherein the plasma

generators are placed side by side on a carrousel of the kinematic system.

23. (Previously presented): A device according to claim 19, wherein the kinematic

system comprises an accumulation zone for grouping the containers and in that a plurality of

generators are positioned above this system for a batch treatment of containers.

24. (Previously presented): A device according to claim 19, wherein the power supply

system comprises a current source and the gas supply system comprises a gas distributor.

25. (Previously presented): A device according to claim 24, wherein the current source,

the gas distributor, and a control unit comprising a microcontroller, are controllable so as to

provide a plasma treatment program for each container, individually.

26. (Previously presented): A device according to claim 25, wherein the current source,

the gas distributor and the microcontroller are provided in the same housing or as blocks above

the container to be treated.

Amendment After Final Office Action mailed December 12, 2007 Serial No. 10/510,999 27. (Previously presented): A device according to claim 23, wherein the kinematic

system comprises a pivoting guide for directing the loading of the containers in the accumulation

zone.

28. (Previously presented): A device according to claim 19, wherein a treatment zone

of the kinematic system comprises rows for storing rows of said containers in such a manner that

the treatment of the containers is carried out therein row by row, as and when the rows are filled

with containers.

29. (Previously presented): A device according to claim 23, further comprising at least

two compartmented complementary zones upstream and downstream of the accumulation zone,

which are used for, respectively, placing the containers in rows in the accumulation zone and

discharging the containers from the accumulation zone.

30. (Previously presented): A device according to claim 19, wherein the power supply

system comprises a central current source comprising a high frequency current generator

producing high frequency electric pulses controlled by signals sent to a gate of a triode, the high

frequency pulses being sent in parallel to each plasma generator to produce, via the LC adapters,

a discharge in the form of a network of filaments in each container.

31. (Previously presented): A device according to claim 19, wherein the power supply

system comprises a central high voltage bipolar direct current source supplying individual high

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speed and high voltage interrupter transistors of each plasma generator.

32. (Previously presented): A device according to claim 19, wherein the power supply

system comprises a central high voltage unipolar direct current source supplying the generators,

the generators being provided with bridges comprising two high speed and high voltage

interrupter transistors adapted to create discharges in the form of a "network of filaments".

33. (Previously presented): A device according to claim 19, wherein the power supply

system comprises a central high voltage direct current source supplying the plasma generators,

the generators being provided with individual field transistor systems, each having a CR

amplitude-phase circuit, with the signal being modulated by a computer, each of said individual

field transistor systems supplying electricity for a discharge in the form of a "network of

filaments" on the inner surface of the container to be treated.

34. (Previously presented): A device according to claim 30, wherein high power

elements of a circuit of the high frequency current generator are cooled in such a manner as to

function in a non-steady heat transfer state.

35. (Previously presented): A device according to claim 19, wherein the kinematic

system comprises pneumatic transport channels (62) in which the containers are moved by an air

stream, the pneumatic transport channels being movable in a plasma treatment zone (20) of the

device, in order to enable the access of the generator electrodes (54a) to the containers.

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36. (Previously presented): A device according to claim 21, wherein the control unit controls the execution of a program of distribution of gas portions to form the gaseous mixture

constituting the treatment gas used in the plasma treatment of the containers.

37. (New): The device of claim 19, wherein said lower electrode being provided with

said rotational mechanism for rotating said container.